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OKADA et al.(10) **Pub. No.: US 2024/0213075 A1**(43) **Pub. Date: Jun. 27, 2024**(54) **SUBSTRATE PROCESSING DEVICE AND
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ABSTRACT

A substrate is held by an upper holding device, and a lower-surface center region of the substrate is cleaned with use of a lower-surface brush. The substrate is lowered from an upper holding device and transferred to a suction holder of a lower holding device. The substrate held by the suction holder is cleaned with use of a processing liquid. A cup is provided to be liftable and lowerable between an upper cup position and a lower cup position. The cup is in the lower cup position when waiting. A period for the substrate lowering operation and a period for the cup lifting operation at least partially overlap with each other.

